

**AMENDMENTS TO THE CLAIMS**

Please amend the claims as follows:

1. (Currently Amended) A resist stripping equipment, comprising:
  - a first stripping solution tank in which resist stripping solution is preserved;
  - a first resist stripping chamber in which a substrate covered with resist is accommodated;
  - a first spray which is connected to the first stripping solution tank and sprays the resist stripping solution into the resist in the first resist stripping chamber;
  - a first solution line which supplies the sprayed resist stripping solution from the first resist stripping chamber to the first resist stripping tank;
  - a gas line which supplies a mixed gas containing a resist stripping solution component from the first resist stripping ~~container~~ chamber to outside;
  - a gas/liquid separation block which is connected to the gas line, and which separates the resist stripping solution component from the introduced mixed gas; ~~and~~
  - a second resist stripping chamber which is connected to the first resist stripping chamber and where to the substrate is supplied from the first resist stripping chamber;
  - a second stripping solution tank in which resist stripping solution is preserved;
  - a second spray which is connected to the second stripping solution tank and sprays the resist stripping solution into the resist in the second resist stripping chamber;
  - a second solution line which supplies the sprayed resist stripping solution from the second resist stripping chamber to the second resist stripping tank;
  - a recovered resist stripping solution line which is connected to the gas/liquid separation block and supplies the separated resist stripping solution component to the second stripping solution tank; ~~and~~
  - a line which is connected to the second stripping solution tank and supplies the resist stripping solution to the first stripping solution tank.

2. (Currently Amended) The resist stripping equipment of claim 1, further comprising:
  - a separated gas supply unit which receives gas separated from the resist stripping solution component in the liquid/gas separation block and supplies the gas to ~~the~~ a gas spout unit,
  - wherein at least one of the resist stripping chambers includes a ~~the~~ gas spout unit.
3. (Original) The resist stripping equipment of claim 2, wherein the gas spout unit is disposed facing the substrate.
4. (Currently Amended) The resist stripping equipment of claim 1, further comprising:
  - an inert gas supply unit which is connected to the resist stripping chambers and supplies inert gas into the resist stripping chambers.
5. (Currently Amended) The resist stripping equipment of claim 4, further comprising:
  - ~~a plurality of~~ the resist stripping chambers provided in multiple stages to communicate with each other;
  - a rinse chamber provided to communicate with one of the ~~plurality of~~ resist stripping chambers at a last stage, the rinse chamber being supplied with water;
  - the gas/liquid separation block connected to one of the ~~plurality of~~ resist stripping chambers at a first stage; and
  - the inert gas supply unit connected to the rinse chamber,
  - wherein the resist stripping solution is a water-based resist solution.
6. (Currently Amended) The resist stripping equipment of claim 4, further comprising:
  - ~~a plurality of~~ the resist stripping chambers provided in multiple stages to communicate with each other;
  - a rinse chamber provided to communicate with one of the ~~plurality of~~ resist stripping chambers at a last stage, the rinse chamber being supplied with water;
  - the gas/liquid separation block connected to one of the ~~plurality of~~ resist stripping chambers at a first stage; and
  - the inert gas supply unit connected to one of the ~~plurality of~~ resist stripping chambers at the last stage,
  - wherein the resist stripping solution is a non-water-based stripping solution.